ERRATA

**Erratum to: “Growth of EuO/Si and EuO/SrO/Si Heteroepitaxial Structures by Molecular-Beam Epitaxy”
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**P. E. Teterin^a, D. V. Averyanov^{a, b}, Yu. G. Sadofyev^{a, c}, O. E. Parfenov^a,
I. A. Likhachev^a, and V. G. Storchak^a**

^a National Research Center “Kurchatov Institute”, Moscow, 123182 Russia

^{e-mail}: teterin_pe@nrcki.ru

^b National Nuclear Research University “MEPHI”, Moscow, 115409 Russia

^c Lebedev Physical Institute, Russian Academy of Sciences, Moscow, 119991 Russia

^{e-mail}: sadofyev@hotmail.com

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Figure 4 should be as follows:

Fig. 4. Spectra of Rutherford backscattering for an Al/EuO/Si sample measured in two modes: random and aligned.